IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
Lee) Group No.: Not Yet Assigned) Previous Group No. 2653
Serial No.: Not Yet Assigned Previous Serial No.: 10/156,633) Examiner: Not Yet Assigned) Previous Examiner: Paul Kim
Filing Date: Not Yet Assigned Previous Filing Date: 05/28/2002)

For: "METHOD OF PROVIDING PROTECTION FOR THE POLE PIECE OF A MAGNETIC HEAD DURING ITS MANUFACTURE WITH USE OF A SELECTIVELY ETCHABLE MATERIAL" (as amended herein)

Previous Title: "METHOD OF PROTECTING THE POLE PIECE OF A MAGNETIC HEAD DURING THE ION MILL PATTERNING OF THE YOKE"

MAIL STOP PATENT APPLICATION Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

PRELIMINARY AMENDMENT

The Applicant respectfully submits this Preliminary Amendment for the above-referenced *DIVISIONAL* patent application which is based on U.S. Application No. 10/156,633 filed on 05/28/2002.

IN THE TITLE

Please delete the current title and substitute therefor –Method Of Providing Protection To The Pole Piece Of A Magnetic Head During Its Manufacture With Use Of A Selectively Etchable Material--.

AFTER THE TITLE

On page 1 after the title, please add the following paragraph:

CROSS-REFERENCE TO RELATED APPLICATION

This application is a divisional application of U.S. patent application having Serial No. 10/156,633 filed on 05/28/2002 entitled "Method Of Protecting The Pole Piece Of A Magnetic Head During The Ion Mill Patterning Of The Yoke".

IN THE SUMMARY

On page 5-6, please replace the current paragraph in the Summary Of The Invention with the following new paragraph:

In one illustrative example of the present invention, a method of making a magnetic head involves providing a partially constructed magnetic head which has a top surface formed by a front P2 pole tip, a back gap P2 pedestal, and insulator materials disposed between the front P2 pole tip and the back gap P2 pedestal; forming a layer of selectively etchable materials over the top surface of the partially constructed magnetic head, the layer having a front edge that is recessed away from an air bearing surface (ABS); forming additional insulator materials over the selectively etchable material layer and over a front portion of the front P2 pole tip; performing a chemical-mechanical polishing (CMP) to form a substantially coplanar top surface with the selectively etchable material layer and the additional insulator materials; etching to remove the selectively etchable material layer; depositing yoke layer materials over the resulting structure; and performing a chemically-mechanically polishing (CMP) to form a substantially coplanar top surface with the yoke layer materials and the additional insulator materials, to thereby form a yoke.